

Attorney Docket: 081468-0275503  
Client Reference: P-0166.010-US

**REPLY UNDER 37 C.F.R. §1.116  
EXPEDITED PROCEDURE  
TECHNOLOGY CENTER ART UNIT 2882**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re PATENT APPLICATION of:  
CASTENMILLER et al.

Confirmation Number: 4742

Application No.: 09/739,622

Group Art Unit: 2882

Filed: December 20, 2000

Examiner: Ho, Allen

Title: POSITION MEASURING SYSTEM FOR USE IN LITHOGRAPHIC APPARATUS  
(As Amended)

**AMENDMENT AFTER FINAL REJECTION UNDER 37 C.F.R. §1.116**

Mail Stop Amendment After Final  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RECEIVED**

**APR 13 2004**

**Technology Center 2800**

Sir:

In response to the Office Action dated January 30, 2004, please amend the above-identified application as follows:

**IN THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently amended) A lithographic projection apparatus comprising:
  - a projection beam illumination system which supplies a projection beam of radiation;
  - a first object table for holding a protection beam patterning device which patterns the projection beam according to a desired pattern;
  - a second object table for holding a substrate; and
  - a projection system which images the patterned beam onto a target portion of the substrate;
  - a reference frame; and